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	Application No.	Applicant(s)
Notice of Allowability	09/874,073	GURER ET AL.
	Examiner	Art Unit
	Ram N Kackar	1763
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT I of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in this 5) or other appropriate communica RIGHTS. This application is subje	application. If not included attaction will be mailed in due course. THIS
1. \square This communication is responsive to <u>8/13/2004</u> .		
2. X The allowed claim(s) is/are 45-47,50,51,63,65-67,70 and	<u>71</u> .	
3. \boxtimes The drawings filed on <u>04 June 2001</u> are accepted by the	Examiner.	
 4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some* c) None of the: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient. 6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted. (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date Lidentifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d). 7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL. 		
Attachment(s) 1. Notice of References Cited (PTO-892)	5. Notice of Inform	nal Patent Application (PTO-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948) 6. Interview Summ	
3. Information Disclosure Statements (PTO-1449 or PTO/SB Paper No./Mail Date 4. Disclosure Statements (PTO-1449 or PTO/SB Paper No./Mail Date		endment/Comment
 Examiner's Comment Regarding Requirement for Deposit of Biological Material 	8. ⊠ Examiner's Stat 9. ☐ Other	ement of Reasons for Allowance
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EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

-- Amend claim 45 as below:

An apparatus for delivering media to a wafer, comprising:

a housing defining a process chamber;

a spin chuck positioned in the process chamber, the spin chuck having a wafer support surface, the wafer support surface coated with a coating layer such that at least a portion of a particulate matter on the wafer support surface is encapsulated by the coating layer; and

a skirt positioned at a periphery and in a non-planer relationship to the wafer support surface such that a magnitude of radial thermal gradients in a wafer positioned on the spin chuck is reduced, wherein a lateral edge of the wafer support surface skirt contacts a lateral edge of the wafer support surface, is in non-mechanical supporting position relative to the wafer and is sized to permit a wafer positioned on the wafer support surface to extend beyond a periphery of the skirt.

- -- Cancel claims 61 and 62.
- -- Amend claim 70 as below:

An apparatus of claim 45 for delivering media to a wafer, comprising:

a housing defining a process chamber; and

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a spin chuck positioned in the process chamber, the spin chuck having a wafer support surface, the wafer support surface coated with a coating layer such that at least a portion of a particulate matter on the wafer support surface is encapsulated by the coating layer; and wherein the wafer support surface includes a line contact vacuum ring.

-- Cancel claim72.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Tom Van Zandt on 9/15/2004.

REASONS FOR ALLOWANCE

2. The following is an examiner's statement of reasons for allowance:

Claim 45 is allowable for the specific structure of the thermal reducing skirt not disclosed or fairly suggested in the prior art in the context of other limitations of this claim.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ram N Kackar whose telephone number is 571 272 1436. The examiner can normally be reached on M-F 8:00 A.M to 5:P.M.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Gregory Mills can be reached on 571 272 1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

RK

P. Hassansadet primary Examiner AV 1763